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(21)Application number : 06-265182 (71)Applicant : FUJI PHOTO FILM CO LTD
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(54) PHOTORESISTIVE RESIN COMPOSITION, COLOR FILTER USING SAME AND ITS PRODUCTION

(57)Abstract:

PURPOSE: To obtain a photosensitive resin compsn. soluble in an aq. alkali soln., having satisfactory alkali resistance after curing, moreover, excellent in solubility and suitability to the production of a resin and excellent also in chemical resistance.

CONSTITUTION: This photosensitive resin compsn. contains a resin having repeating units represented by at least formula I and/or formula II. In the formulae I, II, R1 is H or methyl, R2 is 1-12C alkyl, etc., R3 is H or methyl, X1 is a single bond, -COO-, etc., X2 is a single bond, -COO-, etc., A1 is a trivalent org. group capable of forming an imide ring by a ring-closing reaction of COOH with CONH-R2 and A2 is a divalent org. group capable of forming an imide ring by a ring-closing reaction of COOH with NHCO.

